

Nanometrics Introduces the Lynx™ Metrology System

Versatile Platform Offers Multiple Metrology Capabilities in a Single Tool

Nanometrics Incorporated (Nasdaq: NANO), a leading supplier of advanced process control metrology equipment, today announced the launch of its new Lynx™ metrology platform at SEMICON West 2008.

The Lynx is the industry's first compact 300mm cluster metrology platform to enable thin film, optical critical dimension (OCD) and overlay measurements in a single system. The Lynx's versatility provides for a range of custom configurations, from a streamlined single metrology platform to an expanded, high-productivity, multi-metrology platform. Modules can be easily installed or upgraded to extend system capabilities.

Productivity of the Lynx system is optimized by Nanometrics' proprietary cluster control software, which allows for sequence and recipe customization in a high-volume production environment. The Lynx's compact and versatile cluster architecture provides a significant cost of ownership improvement, with a 30% smaller footprint in the fab, a 30% reduction in tool-to-tool wafer transportation and a 50% reduction in installation and facilities costs.

"The Lynx is the industry's first true mix-and-match metrology system, allowing our customers to configure each tool to exactly suit their sampling and process control needs," said Kevin Heidrich, Nanometrics' senior director of business development. "A single system can run up to 360 wafers per hour across configurations of up to four metrology modules, including IMPULSE™ CD, IMPULSE™ Thin Film, and Caliper InSight™ overlay solutions, greatly enhancing our customers' process development and high-volume production capabilities fabwide."

"So far this year, we have introduced new tools in each of our primary served markets, and we are excited to launch our new Lynx platform at SEMICON West," commented Tim Stultz, president and chief executive officer. "By combining our new products and the Lynx architecture, we enable an optimized solution for every fab segment, providing our customers with the best price/performance process control solution available in the semiconductor industry."

Visit Nanometrics at SEMICON West 2008 in the South Hall of Moscone Center (booth 1407) and at InterSolar 2008 at Moscone West (booth 9846).

Lynx, Caliper InSight, and IMPULSE are trademarks of Nanometrics Incorporated.

About Nanometrics

Nanometrics is a leader in the design, manufacture and marketing of high-performance process control metrology systems used in semiconductor manufacturing. Nanometrics standalone and integrated metrology systems measure various thin film properties, critical dimensions, overlay control and optical, electrical and material properties, including the structural composition of silicon and compound semiconductor devices, during various steps of the manufacturing process. These systems enable semiconductor manufacturers to improve yields, increase productivity and lower their manufacturing costs. The company maintains its headquarters in Milpitas, California, with sales and service offices worldwide. Nanometrics is traded on the NASDAQ Global Market under the symbol NANO. Nanometrics' website is <http://www.nanometrics.com>.

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